

REMARKS

The Examiner's Office Action of June 18, 2003 has been received and its contents reviewed. Applicants would like to thank the Examiner for the consideration given to the above-identified application.

By the above actions, independent claims 1, 6, 12, 17, 23, 28, 34, 39, 45 and 50 have been amended. Accordingly, claims 1-65 are pending for consideration, of which claims 1, 6, 12, 17, 23, 28, 34, 39, 45, 50, 55 and 60 are independent. In view of these actions and the following remarks, reconsideration of this application is now requested.

Referring now to the detailed Office Action, claims 1-65 stand rejected under 35 U.S.C. §102(b) as anticipated by Makita et al. (U.S. Patent No. 5,696,003 - hereinafter Makita). In response to the rejection, Applicants have amended claims 1, 6, 12, 17, 23, 28, 34, 39, 45 and 50, as shown above, to further clarify the claim language. Specifically, the claims have been amended to recite the step of segregating the metal element in the impurity region containing the noble gas element by a second heat treatment.

Applicants respectfully submit that there is no teaching, disclosure, or suggestion in Makita of the steps of forming an impurity region to which a noble gas element is added in the crystalline semiconductor film, or of segregating the metal element in the impurity region containing the noble gas element by a second heat treatment.

Should the Examiner continues to assert that Makita discloses adding a noble gas in forming an impurity region, Applicants respectfully request the Examiner to point out specifically where such a disclosure can be found.

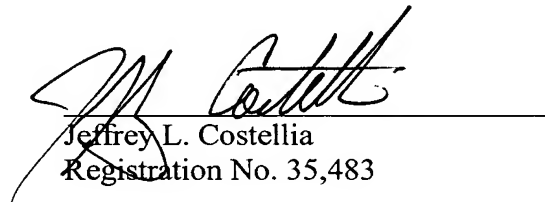
Consequently, since each and every feature of the present claims is not taught (and is not inherent) in the teachings of Makita, as is required by MPEP Chapter 2131 in order to establish anticipation, the rejection of claims 1-65, under 35 U.S.C. §102(b), as anticipated by Makita is improper and must be withdrawn.

Turning now to the IDS submitted on June 27, 2003, Applicants would like note that JP 5-109737 should be reviewed by the Examiner as it discloses getting by argon in paragraph [0007].

In view of the amendments and arguments set forth above, Applicants respectfully requests reconsideration and withdrawal of all the pending §102(b) rejection.

While the present application is now believed to be in condition for allowance, should the Examiner find some issue to remain unresolved, or should any new issues arise, which could be eliminated through discussions with Applicants' representative, then the Examiner is invited to contact the undersigned by telephone in order that the further prosecution of this application can thereby be expedited.

Respectfully submitted,



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